

UNIVERSITÀ DEGLI STUDI DI MILANO

DIPARTIMENTO DI FISICA

Theoretical spectroscopy characterization

of deep electronic states due to implanted Ge atoms in Silicon

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Single atom semiconductor devices based on conventional dopants (As, P) can only operate at cryogenic temperature because of electron ionization at room temperature. Differently, Ge implanted in Si and annealed at 500 °C behaves as a donor having deep levels in the bandgap [3,4]. Such system is a promising candidate to act as atomic center in silicon transistors up to room temperature. However, little is known about excited states and its potential role as coherent spin state center operating up to room temperature. Our purpose is to apply the state of the art ab-initio density-functional based approaches to achieve a correct interpretation of the experimentally measured electronic and transport properties of Si with implanted Ge atoms. In particular we plan to apply hybrid functionals methods that are substantially less demanding than MBPT and allow to obtain quantitatively reliable results for quasiparticle levels together with good structural properties. This work is part of a Italy-Japan joined theoretical and experimental project presented to the NFFA.eu infrastructure.





DEFECT GEOMETRY





Ge atom likely bound to one or more vacancies. Geometrical relaxation at GGA level with SIESTA (pseudopotentials + localized atomic orbital basis set) large unit cell (64, 216, 360 atoms)





Ground state spin state depending on the local geometry Defect states merging to CB in charged defect

- $\alpha E_{HF}^{x} + (\alpha 1) E_{DFT}^{x} + E_{DFT}^{c} \longrightarrow V_{Hybrid}$
- $\alpha = 1/\epsilon_{c}$

Preliminary calculations with hybrid potentials in the small cell (64 atoms) confirms the local geometry relaxation and improves the electronic properties description.



Recent results relative to electronic transport in nanostructures

